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# Back contact interfacial modification mechanism in highlyefficient antimony selenide thin-film solar cells

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**Abstract:** Antimony selenide (Sb<sub>2</sub>Se<sub>3</sub>) is a potential photovoltaic (PV) material for nextgeneration solar cells and has achieved great development in the last several years. The properties of Sb<sub>2</sub>Se<sub>3</sub> absorber and back contact influence the PV performances of Sb<sub>2</sub>Se<sub>3</sub> solar cells. Hence, optimization of back contact characteristics and absorber orientation are crucial steps in raising the power conversion efficiency (PCE) of Sb<sub>2</sub>Se<sub>3</sub> solar cells. In this work, MoO<sub>2</sub> was introduced as an intermediate layer (IL) in Sb<sub>2</sub>Se<sub>3</sub> solar cells, and comparative investigations were conducted. The growth of (211)-oriented Sb<sub>2</sub>Se<sub>3</sub> with large grains was facilitated by introducing the MoO<sub>2</sub> IL with suitable thickness. The MoO<sub>2</sub> IL substantially lowered the back contact barrier and prevented the formation of voids at the back contact, which reduced the thickness of the MoSe<sub>2</sub> interface layer, inhibited carrier recombination, and minimized bulk and interfacial defects in devices. Subsequently, significant optimization enhanced the open-circuit voltage ( $V_{OC}$ ) of solar cells from 0.481 V to 0.487 V, short-circuit current density ( $J_{SC}$ ) from 23.81 mA/cm<sup>2</sup> to 29.29 mA/cm<sup>2</sup>, and fill factor from 50.28% to 57.10%, which boosted the PCE from 5.75% to 8.14%.

#### 1. Introduction

Solar energy holds the promise of carbon-free energy that can be used to meet our energy demands. Si-based solar cells have the highest power conversion efficiency (PCE); it contributes significantly to photovoltaic (PV) devices with a PCE of more than 26.8% [1]. However, the low absorption coefficient and high processing cost of Si are major issues that limit its future application for the development of highly efficient and low-cost PVs. Compound-based solar cells, such as perovskites, copper-indium-gallium-selenide (Cu(In,Ga)Se<sub>2</sub>), and cadmium telluride (CdTe), have attracted huge attention and have attained PCE values higher than 21% [1]. However, the instability of perovskites, the toxic nature of Cd, and the low natural abundances of In and Ga are important issues in scaling up this technology. Therefore, research is being conducted on stable and environment-friendly PV semiconductor materials. Among various photoactive materials, antimony selenide (Sb<sub>2</sub>Se<sub>3</sub>) thin films have an appropriate band gap, suitable absorption coefficient, and good conductivity [2-5]. Furthermore, their high theoretically attainable PCE (more than 30%) makes them potential candidates for the future generation of PVs [6]. Sb<sub>2</sub>Se<sub>3</sub> solar cells have drawn huge interest, and their performances have gradually improved. The reported PCE of Sb<sub>2</sub>Se<sub>3</sub> solar cells have increased promptly from 1.9% to 10.57% [2,3,7–15]. The series-connected antimony selenosulfide monolithic integrated PV minimodules have achieved PCE of 7.15% [16]. Tang's group prepared Sb<sub>2</sub>Se<sub>3</sub> photo-absorber film by thermal evaporation method and obtained 2.1% efficiency [17]. Afterward, the rapid thermal evaporation method was used to tune the crystal orientation of Sb<sub>2</sub>Se<sub>3</sub>, which raised the PCE up to 5.6% [18]. In 2018, the same research group prepared a high-quality Sb<sub>2</sub>Se<sub>3</sub> absorber layer by vapor transporting deposition, and the defect concentration of the Sb<sub>2</sub>Se<sub>3</sub> absorber layer was reduced [3]. The Sb<sub>2</sub>Se<sub>3</sub> device exhibited a PCE of 7.6%. Mai et al. fabricated Sb<sub>2</sub>Se<sub>3</sub> nanorod array by close space sublimation process and gained a much-improved PCE of 9.2% [2]. Chen's group fabricated Sb<sub>2</sub>(S, Se)<sub>3</sub> solar cells with a PCE of 10% by hydrothermal method [19]. However, the PCE values were still considerably

lower than the theoretical limits (PCE = 30%) of the Sb<sub>2</sub>Se<sub>3</sub> device. Sb<sub>2</sub>Se<sub>3</sub> PVs have shown exceptional performances with the device configuration of Mo/Sb<sub>2</sub>Se<sub>3</sub>/CdS/indium tin oxide (ITO)/Ag, similar to CZTS and CdTe solar cells [20,21]. Back contact engineering is one of the best strategies for improving the PV parameters ( $V_{OC}$ ,  $J_{SC}$ , and fill factor (FF)) of chalcogenide thin-film solar cells [22]. The characteristics of Mo/Sb<sub>2</sub>Se<sub>3</sub> back contact play a significant role in photo-generated carrier transport in Sb<sub>2</sub>Se<sub>3</sub> devices, where the low barrier of Mo/Sb<sub>2</sub>Se<sub>3</sub> back contact is important to achieve a high PCE. In addition, a MoSe<sub>2</sub> layer was observed between Sb<sub>2</sub>Se<sub>3</sub> and Mo electrode [23]. A thick MoSe<sub>2</sub> interface layer may be harmful to the transport of carriers at the Mo/Sb<sub>2</sub>Se<sub>3</sub> back contact, which reduces the PCE of Sb<sub>2</sub>Se<sub>3</sub> solar cells. In our previous work, (211)-oriented Mo not only induced the growth of (hk1)-oriented Sb<sub>2</sub>Se<sub>3</sub> but also improved the ohmic contact at the Mo/Sb<sub>2</sub>Se<sub>3</sub> back interface due to the existence of MoSe<sub>2</sub> layer [24]. The ohmic contact of Mo/Sb<sub>2</sub>Se<sub>3</sub> interface can be improved by further reducing the thickness of MoSe<sub>2</sub> interface appropriately. Thus, further optimization of the back contact of Sb<sub>2</sub>Se<sub>3</sub> may lead to the auxiliary promotion of PCE. Relatively, less attention has been given to the modification of back contact  $(Mo/Sb_2Se_3)$  of the device structure of Mo/Sb<sub>2</sub>Se<sub>3</sub>/CdS/ITO/Ag. Mo selenization was used to prepare the MoSe<sub>2</sub> intermediate layer (IL) at the back contact to boost the PCE of Sb<sub>2</sub>Se<sub>3</sub> solar cells, but the PCE of Sb<sub>2</sub>Se<sub>3</sub> solar cells was limited to 5% [25]. Thus, a better back contact modification of Sb<sub>2</sub>Se<sub>3</sub> solar cells is needed for detailed investigation. In this study, we adopted an ambient pre-annealing process to prepare the MoO<sub>2</sub> layer between Sb<sub>2</sub>Se<sub>3</sub> absorber layer and Mo substrate in Sb<sub>2</sub>Se<sub>3</sub> solar cells. The MoO<sub>2</sub> layer suppressed the formation of MoSe<sub>2</sub> interface layer, and the Mo/Sb<sub>2</sub>Se<sub>3</sub> back contact barrier was abridged. Compared with Sb<sub>2</sub>Se<sub>3</sub> solar cells (without MoO<sub>2</sub> IL), the V<sub>OC</sub> of Sb<sub>2</sub>Se<sub>3</sub> solar cells increased from 0.481 V to 0.487 V, the  $J_{SC}$  increased from 23.81 mA/cm<sup>2</sup> to 29.29 mA/cm<sup>2</sup>, and FFFF increased from 50.28% to 57.10%, which led to a final PCE of 8.14% with the MoO<sub>2</sub> IL. Afterward, the effect of MoO<sub>2</sub> IL on the Sb<sub>2</sub>Se<sub>3</sub> properties, interface properties, carrier diffusion length, and defect properties of devices were explored. In addition, the influence of annealing temperature on the thickness of MoO<sub>2</sub> layer was thoroughly investigated.

#### 2. Experimental

#### 2.1. Preparation of MoO<sub>2</sub> intermediate layer

First, substrates (Mo-coated glass) were washed with ethanol, detergent, and distilled water by ultrasonication. The cleaned Mo substrates were annealed in the furnace under the air flow to grow the MoO<sub>2</sub> IL. Here, the annealing temperatures of samples were kept at 300 °C and 400 °C. The annealing duration of samples was 15 min. The unannealed sample was labeled as Mo1, and the samples annealed at 300 °C and 400 °C were respectively labeled as Mo2 and Mo3.

#### 2.2. Preparation of Sb<sub>2</sub>Se<sub>3</sub> thin films

The Sb precursors were prepared on Mo1, Mo2, and Mo3 substrates by radio frequency magnetron sputtering at very low pressure (below  $5.0 \times 10^{-4}$  Pa). The flow rate of Ar was 40 sccm, the sputtering power of Sb was kept at 34 W, the sputtering time of Sb metal precursor was 40 min, and the sputtering pressure for deposition of Sb was 1 Pa. Subsequently, Sb<sub>2</sub>Se<sub>3</sub> was fabricated by post-selenization of the Sb layer. The Se (0.4 g) and Sb metal precursors were kept in the compartment. The evacuation process was conducted, and argon was introduced into the furnace prior to selenization. The selenization pressure for all samples was  $7 \times 10^4$  Pa. The selenization temperature of Sb<sub>2</sub>Se<sub>3</sub> on Mo1, Mo2, and Mo3 substrates was 410 °C. The ramping rate for all selenized samples was 20 °C/min, and the selenization time of all samples was 15 min. Three samples were labeled as S<sub>Mo1</sub>, S<sub>Mo2</sub>, and S<sub>Mo3</sub>.

#### 2.3. Fabrication of Sb<sub>2</sub>Se<sub>3</sub> solar cells

Cadmium sulfide (CdS) as a buffer layer was deposited onto the  $S_{Mo1}$ ,  $S_{Mo2}$ , and  $S_{Mo3}$  samples by a chemical bath deposition method. The mixed solution was prepared by mixing cadmium sulfate (0.015 M), NH<sub>3</sub>OH aqueous solution, water, and thiourea (0.75 M). The Sb<sub>2</sub>Se<sub>3</sub> absorber was vertically dipped in the solution at 85 °C with continuous stirring for at least 9 min. The CdS films were put into the oven for 30 min to remove excess solution from the surface. The Sb<sub>2</sub>Se<sub>3</sub>/CdS heterojunction was heated at 325 °C in a vacuum, and the annealing time of all samples was 5 min. Afterward, the ITO layers were sputtered on the top surface of CdS buffer layers. Sputtering pressure (0.4 Pa), sputtering time (25 min), and sputtering power (120 W) were kept the same for all devices. Finally, the Ag electrodes were deposited by thermal evaporation. The device area measured 0.09 cm<sup>2</sup> after scabbing. The three devices were labeled as  $S_{Mol}$ ,  $S_{Mo2}$ , and  $S_{Mo3}$ .

#### 2.4. Characterizations

The crystal phases of MoO<sub>2</sub> ILs and Sb<sub>2</sub>Se<sub>3</sub> thin films were analyzed by X-ray diffraction (XRD, Ultima-iv) with Cu  $K_{\alpha}$  radiation. To further investigate the crystal phases of MoO<sub>2</sub> thin films, we analyzed the samples by Raman spectroscopy (HORIBA Jobin Yvon, LabRAM HR Evolution) with an excitation wavelength of 532 nm. Film morphologies of samples were obtained by the scanning electron microscopy (SEM, Zeiss SUPRA 55). Energy dispersive Xray spectroscopy (EDS, BRUKER QUANTAX 200) was utilized for the characterization of sample elemental compositions. The transmission electron microscopy (TEM) images of sample cross-sectional morphologies were obtained by FEI Titan Cubed ThemisG2 300 microscope. The samples for TEM imaging were fabricated by a focused ion beam (FEI Scios). The elemental depth distribution of devices was obtained by TEM coupled with EDS. The ohmic contact properties of Mo/Sb<sub>2</sub>Se<sub>3</sub> back contact were tested by a multi-meter (Keithley, 2400 Series). The work functions of samples were analyzed by ultraviolet-photoelectron spectroscopy (UPS, Thermo Scientific ESCALAB 250Xi). The current density-voltage (J-V) of solar cells was measured by a multi-meter (Keithley, 2400 Series) under standard test conditions (100 mW/cm<sup>2</sup>, AM 1.5 G). The dark J-V curves of solar cells were also measured by a multi-meter (Keithley, 2400 Series). A Keithley 2400 source meter and Zolix SCS101 system were used to test the external quantum efficiency (EQE) of solar cells. Temperaturedependent dark J-V measurements were characterized by Lakeshore 325 temperature controller,

and the temperatures were swept from 300 K to 230 K in a step of 10 K. The capacitancevoltage (*C-V*) measurements and drive level capacitance (DLCP) measurements were characterized by a Keithley 4200A-SCS system with JANIS cryogenic platform. The measurement of temperature-dependent  $V_{\rm OC}$  was utilized by the Lakeshore 325 temperature controller. The electrochemical impedance spectroscopy (EIS) of devices was characterized by the CHI600E electrochemical workstation. Temperature-dependent capacitance frequency (*Cf*-*T*) measurements were carried out within the frequency range of 100 Hz to 10 MHz using the same cryostat and cooling system as mentioned above.

#### 3. Result and discussion

XRD analysis was performed to study the effect of air on the annealing of Mo. The XRD results (Fig. S1a) showed the presence of MoO<sub>2</sub> crystal phases (JCPDS#32-0671) at Mo back electrodes. Furthermore, the Raman spectra (Fig. S1b) indicated the formation of MoO<sub>2</sub> phases on the surfaces of Mo substrates. The presence and thickness of MoO<sub>2</sub> ILs are depicted in Fig, S2, where Mo1 represents the sample without air annealing, Mo2 denotes the sample annealed at 300 °C, and the sample annealed at 400 °C was labeled as Mo3. Samples Mo2 and Mo3 exhibited compact and smooth layers of MoO2 having a thickness of 80 and 800 nm, respectively. Fig. 1(a) shows the cross-sectional morphology of the full device (Mo/Sb<sub>2</sub>Se<sub>3</sub>/CdS/ITO/Ag) fabricated on the sample Mo2, which is labeled as S<sub>Mo2</sub>. MoO<sub>2</sub> layer with a thickness of 80 nm can be observed at Sb<sub>2</sub>Se<sub>3</sub>/Mo back electrode. This finding demonstrates that the selenization process has no effect on the thickness of MoO<sub>2</sub> layer. In contrast to the SEM image (Fig. S3) of the S<sub>Mol</sub> device, the MoSe<sub>2</sub> interface layer was not visible at the Mo/Sb<sub>2</sub>Se<sub>3</sub> back contact in the S<sub>Mo2</sub> device. Thus, the MoO<sub>2</sub> layer suppressed the formation of MoSe<sub>2</sub> layer. The (211)-oriented Sb<sub>2</sub>Se<sub>3</sub> has large grains penetrating through the full absorber layer in the  $S_{Mo2}$  device. On the other hand, a comparatively more dominant (221) oriented Sb<sub>2</sub>Se<sub>3</sub> absorber layer can be observed in the SEM image of S<sub>Mo1</sub> devices (Fig. S3),

consistent with the XRD results. According to the literature, the PCE of the Sb<sub>2</sub>Se<sub>3</sub> device with (211)-oriented Sb<sub>2</sub>Se<sub>3</sub> is more dominant than the (221)-oriented Sb<sub>2</sub>Se<sub>3</sub> [26]. In addition to the favored orientation, the back contact of the S<sub>Mo2</sub> device featured a compact and void-free interface (Fig. 1a) in comparison with that of the S<sub>Mo1</sub> device (Fig. S3). These findings demonstrate that the morphology of the Mo/Sb<sub>2</sub>Se<sub>3</sub> back contact was enhanced by the MoO<sub>2</sub> IL. Fig. 1(b) illustrates the J-V characteristic of S<sub>Mo1</sub>, S<sub>Mo2</sub>, and S<sub>Mo3</sub> devices. The S<sub>Mo1</sub> device had a  $V_{OC}$  of 0.481 V, a  $J_{SC}$  of 23.81 mA/cm<sup>2</sup>, a FF of 50.28%, and a PCE of 5.75%. When the MoO<sub>2</sub> IL with a thickness of 80 nm was introduced at the back contact of S<sub>Mo2</sub> device, all the PV parameters of  $S_{Mo2}$  device increased. The  $S_{Mo2}$  device delivered a  $V_{OC}$  of 0.487 V,  $J_{SC}$  of 29.29 mA/cm<sup>2</sup>, and FF of 57.10%, thus achieving a PCE of 8.14%. The  $V_{OC-deficit}$  decreased from 829 mV in S<sub>Mo1</sub> device to 793 mV in S<sub>Mo2</sub> device indicating the better performance due to the MoO<sub>2</sub> introduction. In addition, the MoO<sub>2</sub> layer with a thickness of 800 nm resulted in PV performance degradation. The  $S_{Mo3}$  device obtained a low PCE of 4.18% with a  $V_{OC}$ ,  $J_{SC}$ , and FF of 0.424 V, 21.52 mA/cm<sup>2</sup>, and 45.76%, respectively. The resistances of MoO<sub>2</sub> IL increased as the thickness further increased. The Mo/Sb<sub>2</sub>Se<sub>3</sub> back contact with the high resistance limited the transport of photo-generated carrier, which led to performance degradation. All photovoltaic parameters were shown in Table 1. Fig. S4 summarizes the statistical distribution performances of the device parameters. Fig. 1(c) presents the J-V parameters of S<sub>Mo1</sub> and S<sub>Mo2</sub> devices under light and dark conditions. The existence of a back contact barrier led to the crossover behavior among the light and dark J-V curves besides the double diode performance [27]. Compared with S<sub>Mo2</sub> device with MoO<sub>2</sub> IL, the crossover points occurred at a lower current in the S<sub>Mo1</sub> device. According to the literature, the crossover behavior at a low current is attributed to the high back contact barrier in solar cells [28]. Thus, the high back contact barrier height may be present in S<sub>Mo1</sub> devices. In addition, the collection of photogenerated holes mainly depends on the Mo/MoSe<sub>2</sub> interface. Thus, we further investigated the barrier of Mo/MoSe<sub>2</sub> in the S<sub>Mo1</sub> device. Fig. S5 shows the UPS spectra of MoSe<sub>2</sub>, Sb<sub>2</sub>Se<sub>3</sub>, MoO<sub>2</sub>, and Mo. The barrier heights

of Mo/MoSe<sub>2</sub>, Mo/MoO<sub>2</sub>, and MoO<sub>2</sub>/Sb<sub>2</sub>Se<sub>3</sub> were 0.55, 0.02, and 0.03 eV, respectively. Fig. 1(d and e) presents the band diagrams of S<sub>Mo1</sub> and S<sub>Mo2</sub> devices. Fig. S6 reveals the effects of the MoO<sub>2</sub> layer on the EQE of solar cells, band gap, and Urbach energy of the absorber. Figs. S6(a and b) show the EQE of S<sub>Mo1</sub> and S<sub>Mo2</sub> devices, respectively. The EQE results demonstrate that the  $S_{Mo2}$  device had a higher  $J_{SC}$  than the  $S_{Mo1}$  device due to its superior carrier collection efficiency. Better crystal orientation improved crystalline quality, and a reduced MoSe<sub>2</sub> interface layer all contributed to the improved  $J_{SC}$ , which also resulted in a higher FF [28]. The band gaps of  $Sb_2Se_3$  in  $S_{Mo1}$  and  $S_{Mo2}$  devices measured 1.31 and 1.28 eV, respectively (Fig. S6c). Thus, the MoO<sub>2</sub> IL can change the band gap of the  $Sb_2Se_3$  absorber layer. Fig. S6(d) shows the Urbach energy  $(E_u)$  of Sb<sub>2</sub>Se<sub>3</sub> attained from EQE. The  $E_u$  parameter is used to evaluate the band tail states because of impurities, defects, and disorders in photo-absorber materials [24]. An  $E_u$  of 22.3 meV indicated the reduction of defect states due to the introduction of MoO<sub>2</sub> IL. The roles of MoO<sub>2</sub> IL include obtaining the ideal orientation of Sb<sub>2</sub>Se<sub>3</sub>, limiting the growth of MoSe<sub>2</sub> interface layer, lowering the back contact barrier, promoting grain growth, and increasing minority carrier diffusion length. These functions of MoO<sub>2</sub> IL in the device need to be investigated in detail.

Fig. 2(a) shows the XRD data of the Sb<sub>2</sub>Se<sub>3</sub> film on Mo1, Mo2, and Mo3 substrates. All the peaks of S<sub>Mo1</sub>, S<sub>Mo2</sub>, and S<sub>Mo3</sub> samples were in good match with JCPDS (No. 15-0861) with no secondary phases. Each sample exhibited the preferred (211), (221), and (002) orientations of Sb<sub>2</sub>Se<sub>3</sub> with minimal fluctuation, which is expected to demonstrate variation in the solar cell performance. Compared with S<sub>Mo1</sub>, the I(211)/I(221) intensity ratio of S<sub>Mo2</sub> sample increased from 1.01 to 1.28, inducing the formation of (211)-oriented Sb<sub>2</sub>Se<sub>3</sub> layer upon the insertion of 80 nm MoO<sub>2</sub> IL. However, an extremely thick MoO<sub>2</sub> layer reduced the I(211)/I(221) intensity ratio from 1.28 to 0.87. Thus, an overly thick MoO<sub>2</sub> layer limits the growth of (hk1)-oriented Sb<sub>2</sub>Se<sub>3</sub>. These findings were further authenticated by evaluating the texture coefficient (TC) of Sb<sub>2</sub>Se<sub>3</sub> peaks (Fig. 2b), which can be calculated by Equation (1) [29]

$$TC_{hkl} = \frac{I_{(hkl)}}{I_{0(hkl)}} \left/ \left( \frac{1}{N} \sum_{i=1}^{N} \frac{I_{(h_i k_i l_i)}}{I_{0(h_i k_i l_i)}} \right)$$
(1)

where the peak intensities of planes hkl are  $I_{0(hkl)}$  and  $I_{(hkl)}$  in the standard and measured XRD patterns of Sb<sub>2</sub>Se<sub>3</sub> thin films, respectively. A large TC value indicates the preferred orientation along a specific direction [30]. Compared with S<sub>Mo1</sub> and S<sub>Mo3</sub> samples, the TC value of S<sub>Mo2</sub> sample's (211) peak was higher. When the thickness (MoO<sub>2</sub>) increased from 0 nm to 80 nm, the TC value of S<sub>Mo2</sub> sample's (211) peak increased and then declined with the further increase in thickness. Fig. 2(c-e) displays the images of surface morphologies of S<sub>Mo1</sub>, S<sub>Mo2</sub>, and S<sub>Mo3</sub> samples. Alongside the preferred orientation, the S<sub>Mo2</sub> sample also showed compact, flat, and large-grained surface morphology, whereas the other two samples comprised comparatively smaller grains and several voids (Fig. 2c-e). Fig. 2(f) shows the plotted porosity and average crystal size of Sb<sub>2</sub>Se<sub>3</sub>, which indicates that the S<sub>Mo2</sub> sample had larger crystal sizes and fewer pin holes. These results demonstrated that the MoO<sub>2</sub> IL with 80 nm-thickness was obliged to the growth of (211)-oriented Sb<sub>2</sub>Se<sub>3</sub> with large grains. The champion S<sub>Mo2</sub> sample was Sb-poor and Se-rich as listed in Table S1.

To further study the interface morphologies of Mo/Sb<sub>2</sub>Se<sub>3</sub> in S<sub>Mo2</sub> solar cells, we captured the TEM images of S<sub>Mo2</sub> devices (Fig. 3). ITO, window layer, a buffer layer (CdS), Sb<sub>2</sub>Se<sub>3</sub> absorber layer, MoO<sub>2</sub> IL, and Mo back electrode of S<sub>Mo2</sub> device were observed from the top to the bottom in Fig. 3(a). High-angle annular dark field scanning–transmission electron microscopy) was performed at the heterojunction interface of Sb<sub>2</sub>Se<sub>3</sub>/CdS in Fig. 3(b). The interface of Sb<sub>2</sub>Se<sub>3</sub>/CdS was indistinct, which implies less lattice mismatch between Sb<sub>2</sub>Se<sub>3</sub> and CdS. Fig. 3(c) shows the TEM image of back contact (Mo/MoO<sub>2</sub>/Sb<sub>2</sub>Se<sub>3</sub>). A distinct interfaces. The absence of dislocation, amorphous layer, or crystal lattice distortion at the Mo/MoO<sub>2</sub> and MoO<sub>2</sub>/Sb<sub>2</sub>Se<sub>3</sub> interfaces is expected to be applied to establish efficient charge carrier generation and transport. Fig. 3(d-f) displays the high-resolution TEM images of Sb<sub>2</sub>Se<sub>3</sub> absorber layer,

MoO<sub>2</sub> IL, and Mo electrode in the device. To further examine the preferred orientation of each layer, we examined the electron diffraction patterns of Sb<sub>2</sub>Se<sub>3</sub>, MoO<sub>2</sub>, and Mo using Fourier transform (Fig. 3g–i). In Fig. 3(g), the (221), (211), and (002) planes of Sb<sub>2</sub>Se<sub>3</sub> can be observed. Fig. 3(h) illustrates the (011), (-211), and (022) planes of MoO<sub>2</sub>, whereas Fig. 3(i) illustrates the (110) and (211) planes of Mo. These results for electron diffraction patterns were consistent with the XRD findings. The TEM-coupled EDS elemental line scans were used to explore the effect of IL (MoO<sub>2</sub>) on the element distribution of device back contact (Fig. S7). The thickness of MoO<sub>2</sub> was about 90 nm. The distribution of Mo at the Mo/Sb<sub>2</sub>Se<sub>3</sub> interface implied that Mo is very stable during selenization. The Sb, Se, and O atoms diffused into the Mo electrode. The diffusion of Sb, Se, and O atoms may have no influence on the PV properties of Sb<sub>2</sub>Se<sub>3</sub>.

To elucidate the role of MoO<sub>2</sub> IL on the back contact barrier of Sb<sub>2</sub>Se<sub>3</sub> device, we studied the ohmic contact of Mo/Sb<sub>2</sub>Se<sub>3</sub> and series resistance ( $R_s$ ). Fig. S8(a) shows the *I-V* curves obtained from the device structure of glass/Mo/Sb<sub>2</sub>Se<sub>3</sub>/Ag. All linear curves (I-V) suggest ohmic contact formation at the Mo/Sb<sub>2</sub>Se<sub>3</sub> interface. Fig. S8(b) illustrates the resistance curves and slopes of all samples. The slopes of S<sub>M01</sub>, S<sub>M02</sub>, and S<sub>M03</sub> measured 0.071, 0.101, and 0.039 S, respectively. Their corresponding resistances were 14.08, 9.90, and 25.64  $\Omega$ . The S<sub>Mo2</sub> device exhibited the largest slope indicating the lowest resistivity and it can improve the ohmic behavior at the Mo/MoO<sub>2</sub>/Sb<sub>2</sub>Se<sub>3</sub> back contact which is favorable for the efficient transport of photogenerated holes [24]. J-V-T curves of devices were also characterized at the temperature range of 230-300 K in a dark environment (Fig. 4a and b).  $R_s$  and barrier heights of the back contact diode were obtained from the result of dark J-V-T [31,32]. Fig. 4(c) shows the temperature-dependent  $R_{\rm s}$ . The  $R_{\rm s}$  of the S<sub>Mo1</sub> device increased 20 times from 300 K to 230 K, compared with the 4 times increased observed for the  $S_{Mo2}$  device. The contact barrier ( $\Phi_B$ ) at the Mo/Sb<sub>2</sub>Se<sub>3</sub> led to a high  $R_{\rm s}$  value at low temperatures. The transport of photogenerated carriers was suppressed by hindering the contact barrier. At low temperatures, the back contact diode term is dominated by fitting the corresponding linear region of ln ( $R_sT$ ) versus 1/T plot in Fig. 4(d). The  $\Phi_B$  of S<sub>Mo1</sub>

and S<sub>Mo2</sub> devices were 217 and 73.9 meV, respectively. The smaller barrier existed at the back contact of S<sub>Mo2</sub> device. In addition, the J-V-T analysis was a useful method used to determine a dominant recombination path present in Sb<sub>2</sub>Se<sub>3</sub> solar cells by plotting  $A \ln(J_0)$  against 1/kT (Fig. 4e). The  $A\ln(J_0)$  versus 1/kT data should yield a straight line and extrapolate to the activation energy  $E_A/q$  at T=0 K. The activation energy ( $E_A$ ) of recombination for the S<sub>Mo1</sub> device was 0.71 eV, and that for S<sub>Mo2</sub> device was 1.18 eV. The bandgap of Sb<sub>2</sub>Se<sub>3</sub> thin films can be obtained from EQE, and the calculated bandgaps of S<sub>Mo1</sub> and S<sub>Mo2</sub> were 1.31 and 1.28 eV, respectively (Fig. S6). The  $E_A$  for the S<sub>Mo1</sub> device was considerably lower than the band gap of Sb<sub>2</sub>Se<sub>3</sub> in S<sub>Mo1</sub> device, which suggests that the recombination mechanism of S<sub>Mo1</sub> device was mainly influenced by interface recombination. The  $E_A$  for the  $S_{Mo2}$  device was relatively close to the band gap of Sb<sub>2</sub>Se<sub>3</sub> in S<sub>Mo2</sub> device, which signified the passivation of recombination at the interface. Fig. 4(f) presents a model of the back contact junction of Sb<sub>2</sub>Se<sub>3</sub> solar cell as a Schottky diode. The circuit model includes two diodes: the main solar cell diode ( $D_{SC}$ ) and back contact diode  $(D_{BC})$  [31]. When the solar cell is forward-biased, the back contact diode is in reverse bias. The reversed biased  $D_{\rm BC}$  is detrimental to the output of photo-generated current. Therefore, MoO<sub>2</sub> IL reduces the back contact barrier value, which significantly mitigates the depraved effect of reversed biased  $D_{\rm BC}$  on the output of photo-generated current.

The interfacial defects and bulk defects of  $S_{Mo1}$  and  $S_{Mo2}$  devices were also investigated by *C*-*V* and DLCP measurements (Fig. 5a). The DLCP ( $N_{DLCP}$ ) is solely sensitive to responses from bulk defects and free carriers, whereas the *C*-*V*( $N_{C-V}$ ) theoretically incorporates responses from interfacial defects, bulk defects, and free carriers [6,10]. Thus, the interfacial defects of Sb<sub>2</sub>Se<sub>3</sub>/CdS were calculated from  $N_{C-V}$ - $N_{DLCP}$  at zero V. The plots of  $N_{C-V}$  and  $N_{DLCP}$  for S<sub>Mo1</sub> and S<sub>Mo2</sub> devices can be obtained from Equation 2 [33]:

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$$\begin{cases} N_{\text{C-V}} = \frac{-2\varepsilon_{\text{r,n}}N_{\text{D}}}{\left(\frac{d(1/C^2)}{dV}\right)qA^2\varepsilon_0\varepsilon_{\text{r,n}}\varepsilon_{\text{r,p}}N_{\text{D}} + 2\varepsilon_{\text{r,p}}} \\ N_{\text{DLCP}} = -\frac{C_0^3}{2q\varepsilon_0\varepsilon_{\text{r,p}}A^2C_1} \\ x = \varepsilon_0\varepsilon_{\text{r,p}}A/C_0 \end{cases}$$
(2)

where A is the area of solar cells,  $N_{\rm D}$  is the carrier concentration of CdS,  $\varepsilon_0$  is the permittivity of free space, and  $\varepsilon_{r,n}$  and  $\varepsilon_{r,p}$  are the relative permittivities of CdS and Sb<sub>2</sub>Se<sub>3</sub> respectively.  $C_0$  and  $C_1$  were quadratic fitting parameters attained from the C-V data. The low discrepancy between the results of DLCP and the C-V of S<sub>Mo2</sub> indicated minor interfacial defect concentration and less interface recombination than S<sub>Mo1</sub> at the Sb<sub>2</sub>Se<sub>3</sub>/CdS interface. The concentrations of interfacial defect for  $S_{Mo1}$  and  $S_{Mo2}$  devices were  $1.91 \times 10^{16}$  and  $5.50 \times 10^{15}$ cm<sup>-3</sup>, respectively. Moreover, the  $S_{Mo2}$  device possessed a larger depletion width ( $W_d$ ) as compared with S<sub>Mo1</sub> which was reasonable to occur since it varied positively with built-in voltage  $(V_{bi})$ , indicating the improved carrier transport in this high built-in electrical field, which improves the carrier transports. To further analyze the depletion region information and the mechanism behind the enhanced device performance, we performed C-V measurements. Fig. 5(b) shows the  $1/C^2$ -V curves. The  $V_{bi}$  extracted from the extended slope of the curves to the xaxis intercept for S<sub>Mo1</sub> and S<sub>Mo2</sub> devices were 533 and 582 mV, respectively. The MoO<sub>2</sub> IL improved the growth quality of Sb<sub>2</sub>Se<sub>3</sub> absorber layer, which optimized the Sb<sub>2</sub>Se<sub>3</sub>/CdS heterojunction interface qualities. Thus, the  $MoO_2$  IL increased the built-in voltage ( $V_{bi}$ ) of  $Sb_2Se_3$  solar cells, which led to the increased  $V_{OC}$ ,  $J_{SC}$ , and FF of  $S_{Mo2}$ .

To further study the effect of  $MoO_2$  IL on the bulk defect of  $Sb_2Se_3$ , we used admittance spectroscopy measurement to examine the energy levels of defects in the bandgap and defect density in the device. Fig. 5(c and d) shows the capacitance-frequency (*C-f*) results of  $S_{Mo1}$  and  $S_{Mo2}$  devices measured at different temperatures from 300 K to 180 K with an increment of 5 K. One defect level was witnessed in  $S_{Mo1}$  and  $S_{Mo2}$  devices. The inflection point corresponding to the admittance spectrum was determined by the Arrhenius plot. Its frequency value ( $\omega_0$ ) was obtained from the angular frequency point  $\omega$  at the maximum of the  $\omega dC/d\omega$  plot. The defect activation energies ( $E_a$ ) were calculated from the slopes of Arrhenius plots that were linearly fitted based on Equation 3 [34–36].

$$\omega_0 = 2\pi v_0 T^2 \exp(\frac{-E_a}{kT})$$
(3)

where  $v_0$  is the attempt-to-escape frequency,  $\omega_0$  is the inflection point frequency, k is the Boltzmann constant, and  $E_a$  is the defect activation energy representing the average defect energy level relative to the valence band maximum or conduction band minimum. According to the literature, the defect in the S<sub>Mo1</sub> device with an  $E_a$  of 321 meV and the fault in the S<sub>Mo2</sub> device with an  $E_a$  of 311 meV can be both referred to as Se vacancy ( $V_{Se}$ ) (Fig. 5e) [37,38]. To further gain insights, we Gaussian fitted the distribution of each defect type using the Kimerling model based on the following equations [39].

$$E(\omega) = kT \ln(\frac{2\pi v_0 T^2}{\omega})$$
(4)

$$N_{t}(E(\omega)) = -\frac{V_{d}}{q\omega} \frac{dC}{d\omega} \frac{\omega}{kT}$$
(5)

where built-in potential, angular frequency, and defect density are denoted as  $V_d$ , and  $\omega$ , and  $N_t(E(\omega))$ , respectively. The defect densities of  $E_a$  values are given in Fig. 5(f). The calculated defect densities of  $S_{Mo1}$  and  $S_{Mo2}$  devices were  $1.91 \times 10^{16}$  and  $6.64 \times 10^{15}$  cm<sup>-3</sup>, respectively. The MoO<sub>2</sub> IL reduced the device's defect density, resulting in less recombination at the interfacial and photo-absorber layers (Table 2).

Furthermore, carrier properties were obtained from temperature-dependent  $V_{OC}$  measurement. Fig. 6(a) illustrates the  $E_a$  of the main recombination in the solar cell.  $E_a$  of  $S_{Mo1}$  and  $S_{Mo2}$  devices were 0.95 and 1.16 eV, respectively. In comparison with that of  $S_{Mo1}$  device, the  $E_a$  of  $S_{Mo2}$  device was relatively close to the band gap of  $Sb_2Se_3$  (1.28 eV), which indicates weaker interfacial recombination in the  $S_{Mo2}$  device. For further study of the interface charge properties of devices, EIS measurements were used to characterize the  $Sb_2Se_3/CdS$  interface. Fig. 6(b) shows the Nyquist plots and the equivalent circuit model are illustrated. Recombination resistances (*R*) in  $S_{Mo1}$  and  $S_{Mo2}$  devices were calculated to be 17251 and 29717  $\Omega$ , respectively, and they were attained from the diameter of the arc. The higher *R* in  $S_{Mo2}$  confined the charge recombination at the  $Sb_2Se_3/CdS$  interface, which resulted in improved  $V_{OC}$ ,  $J_{SC}$ , and FF. To further authenticate the boosted performance of  $S_{Mo2}$ , we systematically investigated the quality of the PN junction of  $S_{Mo1}$  and  $S_{Mo2}$  devices. Fig. 6(c) illustrates the dark *J-V* curves of  $S_{Mo1}$ and  $S_{Mo2}$  devices. Shunt conductance (*G*), diode ideality factor (*A*), series resistance (*R*), and reverse-saturation current density ( $J_0$ ) were obtained from Equation (6) [40].

$$J = J_0 \exp\left[\frac{q}{AkT}(V - RJ)\right] + GV - J_L$$
(6)

Fig. 6(d) shows the dJ/dV versus V plot. The G values of  $S_{Mo1}$  and  $S_{Mo2}$  devices were 11.05 and 6.23 mS/cm<sup>2</sup>, respectively. Both parameters (R and A) of the devices were obtained from dV/dJ against  $(J+J_{SC})^{-1}$  (Fig. 6e). The R of  $S_{Mo1}$  and  $S_{Mo2}$  devices were 5.05 and 2.89  $\Omega$ ·cm<sup>2</sup>, respectively. The resulting value of R in  $S_{Mo2}$  device was smaller than that of  $S_{Mo1}$  device. In addition, the A of  $S_{Mo1}$  and  $S_{Mo2}$  devices were 2.34 and 1.79, respectively, implying the less interface recombination in  $S_{Mo2}$  device. By plotting  $\ln(J+J_{SC}-GV)$  versus V-RJ (Fig. 6f), the  $J_0$  values of  $1.1 \times 10^{-3}$  and  $8.94 \times 10^{-4}$  mA/cm<sup>2</sup> were observed for  $S_{Mo1}$  and  $S_{Mo2}$  devices, respectively. Compared with the  $S_{Mo1}$  device, the  $S_{Mo2}$  device with MoO<sub>2</sub> IL had lower G, R, and A, which confirmed the improved Sb<sub>2</sub>Se<sub>3</sub>/CdS heterojunction quality.

#### 4. Conclusions

In summary, we systematically improved the PV properties of  $Sb_2Se_3$  solar cells by introducing  $MoO_2$  IL to optimize  $Sb_2Se_3$  crystal growth and back contact properties.  $MoO_2$  IL successfully reduced the thickness of the  $MoSe_2$  interface layer, and less void can be observed at the

Mo/Sb<sub>2</sub>Se<sub>3</sub> interface. The back contact barrier of Mo/Sb<sub>2</sub>Se<sub>3</sub> was lowered by the MoO<sub>2</sub> IL, which significantly increased the FF of the solar cell. The growth of (211)-oriented Sb<sub>2</sub>Se<sub>3</sub> with large grains was induced by the MoO<sub>2</sub> IL. In addition, the introduction of MoO<sub>2</sub> IL not only improved the minority carrier diffusion length but also reduced the bulk defects of Sb<sub>2</sub>Se<sub>3</sub> and interface defects at Sb<sub>2</sub>Se<sub>3</sub>/CdS, which inhibited the recombination of devices and improved the carrier transport. Thus, compared with that of S<sub>Mo1</sub> solar cells without MoO<sub>2</sub> IL, the  $V_{OC}$  of the S<sub>Mo2</sub> with MoO<sub>2</sub> layer increased from 0.481 V to 0.487 V and  $J_{SC}$  from 23.81 mA/cm<sup>2</sup> to 29.29 mA/cm<sup>2</sup> and attained a champion PCE of 8.14%. Our work provides an effective method to regulate Sb<sub>2</sub>Se<sub>3</sub> crystal growth and back interface properties by introducing MoO<sub>2</sub> IL for highly efficient Sb<sub>2</sub>Se<sub>3</sub> devices.

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Devices	$V_{\rm OC}({ m V})$	$J_{\rm SC}~({\rm mA/cm^2})$	FF (%)	PCE (%)
S <sub>Mo1</sub>	0.481	23.81	50.28	5.75
$S_{Mo2}$	0.487	29.29	57.10	8.14
S <sub>Mo3</sub>	0.424	21.52	45.76	4.18

Table 1. The photovoltaic parameters of  $S_{Mo1},\,S_{Mo2}$  and  $S_{Mo3}$  devices.

Table 2. Summary of the results derived from CV, DLCP and AS measurement.

Devices	N <sub>CV</sub> (cm <sup>-3</sup> )	N <sub>DLCP</sub> (cm <sup>-3</sup> )	Interface defect density (cm <sup>-3</sup> )	V <sub>bi</sub> (mV)	W <sub>d</sub> (nm)
S <sub>Mo1</sub>	8.11×10 <sup>16</sup>	6.20×10 <sup>16</sup>	1.91×10 <sup>16</sup>	533	0.281
S <sub>Mo2</sub>	6.71×10 <sup>16</sup>	6.16×10 <sup>16</sup>	5.50×10 <sup>15</sup>	582	0.290



Fig. 1. (a) Cross-sectional SEM image of  $S_{Mo2}$  device. (b) *J-V* curves of  $S_{Mo1}$ ,  $S_{Mo2}$  and  $S_{Mo3}$  devices. (c) *J-V* curves of  $S_{Mo1}$  and  $S_{Mo2}$  devices under light and dark states. (d) The band diagrams of  $S_{Mo1}$ . (e) The band diagrams of  $S_{Mo2}$  devices.



Fig. 2. (a) XRD patterns of  $Sb_2Se_3$  thin films. (b) Texture coefficients of the diffraction peaks of  $Sb_2Se_3$  thin films. (c-e) Surface morphologies of  $Sb_2Se_3$  thin films. (f) The average crystal sizes and porosity of  $Sb_2Se_3$  thin films.



**Fig. 3.** (a) Cross-sectional TEM image of S<sub>Mo2</sub> device. (b) Sb<sub>2</sub>Se<sub>3</sub>/CdS interface TEM image. (c) Mo/MoO<sub>2</sub>/Sb<sub>2</sub>Se<sub>3</sub> back contact TEM images. (d-f) High-resolution TEM images of Sb<sub>2</sub>Se<sub>3</sub> absorber layer, MoO<sub>2</sub>/Sb<sub>2</sub>Se<sub>3</sub> interface, and Mo/MoO<sub>2</sub> interface. (g-i) The SAED patterns of Sb<sub>2</sub>Se<sub>3</sub> absorber layer, MoO<sub>2</sub>/Sb<sub>2</sub>Se<sub>3</sub> interface, and Mo/MoO<sub>2</sub> interface.



Fig. 4. (a and b) Temperature-dependent dark current density vs voltage characteristics for a temperature range of approximately 300 to 230 K for devices. (c) Temperature-dependent  $R_s$  of the devices. (d) Blocking contact barrier height of the devices. (e) Aln( $J_0$ ) vs 1/kT plot of S<sub>Mol</sub> and S<sub>Mo2</sub> devices. (f) Circuit model illustrating the solar cell diode ( $D_{SC}$ ), photogenerated current source ( $J_L$ ), and the lumped-series resistance ( $R_S$ ) consisting of background or residual series resistance ( $R_0$ ) and a blocking back contact diode ( $D_{BC}$ ).



Fig. 5. (a) *C*-*V* and *DLCP* profiles of the  $S_{Mo1}$  and  $S_{Mo2}$  devices. (b)  $1/C^2$ -*V* plots of the  $S_{Mo1}$  and  $S_{Mo2}$  devices. (c and d) Temperature-dependent admittance results for the  $S_{Mo1}$  and  $S_{Mo2}$  devices. (e) Arrhenius plots of  $\omega_0/T^2$  versus 1000/T for two devices; the defect activation energies (*E*<sub>a</sub>) were calculated for the defect and are shown inside the figure. (f) Defect densities and defect activation energies (*E*<sub>a</sub>) of  $S_{Mo1}$  and  $S_{Mo2}$  devices derived from the admittance spectra.



**Fig. 6.** (a) Temperature-dependent  $V_{OC}$  measurements. (b) Nyquist plots of  $S_{Mo1}$  and  $S_{Mo2}$  devices. (c) Dark *J-V* curves of  $S_{Mo1}$  and  $S_{Mo2}$  devices. (d) Shunt conductance *G* of  $S_{Mo1}$  and  $S_{Mo2}$  devices. (e) Series resistance *R* and ideality factor *A* of  $S_{Mo1}$  and  $S_{Mo2}$  devices. (f) Reverse saturation current density  $J_0$  of  $S_{Mo1}$  and  $S_{Mo2}$  devices.

Graphical abstract



The  $MoO_2$  intermediate layer enhanced the growth of (211) oriented  $Sb_2Se_3$  absorber and the transport of photo-generated hole at the back contact. The power conversion efficient (PCE) of  $Sb_2Se_3$  solar cell was improved to 8.14 %.

### **Supporting Information**

# Back contact interfacial modification mechanism in highyefficient antimony selenide thin-film solar cells

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Table S1. EDS results for  $Sb_2Se_3$  thin films with different Mo substrates.

Sample	Sb (at. %)	Se (at. %)	Sb/Se ratio
S <sub>Mo1</sub>	35.54	64.46	0.55
$S_{Mo2}$	38.09	61.91	0.62
S <sub>Mo3</sub>	40.68	59.32	0.69



**Fig. S1.** (a) XRD patterns of Mo1, Mo2, and Mo3 substrates, and (b) Raman spectra of the surface of Mo1, Mo2, and Mo3 substrates.



Fig. S2. (a-b) Surface SEM images of Mo substrates, and (d-f) cross-sectional SEM images of Mo substrates

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WO- MoO<sub>2</sub> intermediate layer

Fig. S3. Cross-sectional SEM image of  $S_{Mo1}$  device (WO-MoO<sub>2</sub> intermediate layer)



**Fig. S4.** Statistical distribution of the devices performance parameters including (a) open-circuit voltage ( $V_{OC}$ ), (b) short-circuit current density ( $J_{SC}$ ), (c) fill factor (FF), and (d) power conversion efficiency (PCE).



Fig. S5. UPS spectra for (a) the surface of  $MoSe_2$  interface layer, (b) the back of  $Sb_2Se_3$  layer in  $S_{Mo2}$  device, (c) the surface of  $MoO_2$  intermediate layer, and (d) the surface of Mo.



**Fig. S6.** (a) EQE and integarated  $J_{SC}$  of  $S_{Mo1}$  device, (b) EQE and integarated  $J_{SC}$  of  $S_{Mo2}$  device, (c) bandgap obtained from the EQE of solar cells, and (d) Urbach energy ( $E_u$ ) obtained from the EQE of solar cells.



Fig. S7. EDS element depth profiles of Mo, O, Sb and Se elements in  $S_{Mo2}$  device.



**Figure S8.** (a) *I-V* curves of Mo/Sb<sub>2</sub>Se<sub>3</sub> back contact (the schematic diagram of structure used to test *I-V* curves was inserted). (b) The slopes and resistance curves of  $S_{Mo1}$ ,  $S_{Mo2}$ , and  $S_{Mo3}$  samples.

#### Highlights

- $\Box$  MoO2 layer induces the growth of (211) oriented Sb2Se3 with large grains.
- □ Low back contact barrier can be achieved by introducing the MoO2 layer.
- □ The carrier recombination, bulk and interfacial defects can be passivated.
- □ Highly efficiency of 8.14% obtained by back contact optimization.

#### **Declaration of interests**

 $\boxtimes$  The authors declare that they have no known competing financial interests or personal relationships that could have appeared to influence the work reported in this paper.

 $\Box$  The authors declare the following financial interests/personal relationships which may be considered as potential competing interests: